

Supplementary Information

Highly sensitive hydrazine chemical sensor based on ZnO nanorods field-effect transistor

Rafiq Ahmad,^a Nirmalya Tripathy,^a Da-Un-Jin Jung,^b and Yoon-Bong Hahn^{a,b,*}

^aDept. of BIN Fusion Technology, ^bSchool of Semiconductor and Chemical Engineering, and Semiconductor Physics Research Center, Chonbuk National University, 567 Baekje-daero, Deokjin-gu, Jeonju 561-756, Republic of Korea.

* Corresponding author. E-mail: ybhahn@chonbuk.ac.kr.

Table of contents

1. ZnO NRs adhesion test	S2
2. Transfer characteristic	S3
3. Table-S1: Comparison of the ZnO NRs based FET with amperometric hydrazine sensors	S4
4. Reference	S4

1. ZnO NRs adhesion test

The established tight contact between the directly grown ZnO NRs and electrode were tested using adhesion-testing tape. From the FESEM image (Figure S2), the structural morphology of the as-grown ZnO NRs after testing with adhesion-testing tape was found to be similar without any changes. Thus, it confirms the stability of the vertically grown ZnO NRs, which also helps in fast electron transport due to large surface area.

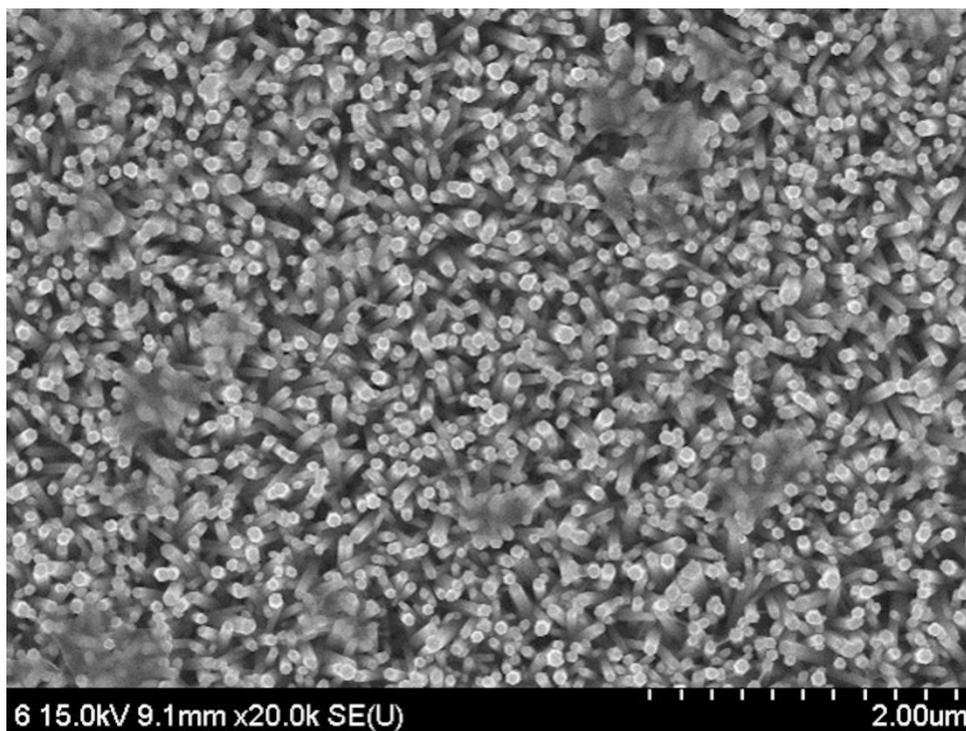


Fig. S1 FESEM image of ZnO NRs taken after adhesion tape test.

2. Transfer characteristic

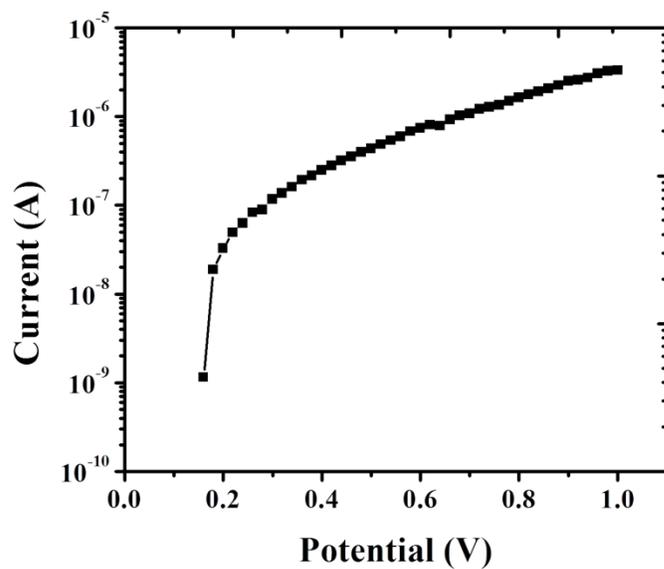


Fig. S2 Transfer characteristic curve of the FET based hydrazine sensor in the presence of 5 μ M hydrazine in 0.01 M PBS at $V_g = 0.1$. The calculated on/off ratio is $\sim 10^4$.

3. Table-S1: A response comparison of the ZnO NRs based FET with various ZnO nanostructure based amperometric hydrazine sensors.

Electrode materials	Sensitivity ($\mu\text{A}/\text{cm}^2 \mu\text{M}$)	Detection limit (μM)	Response time (s)	Linear range (μM)	Ref.
ZnO nanonails	8.56	0.2	<5	0.1-1.2	2
ZnO nanorods	4.76	2.2	<10	0.2-2.0	3
ZnO nanorods	~0.044	~515.7	10	0.3-300	4
ZnO nanoparticles	97.133	0.14754	<5	0.1-10	5
ZnO nanoflower	0.2469	0.18	<3	0.6-250	6
Pristine ZnO nanorods arrays on alloy	4.48	0.2	<8	0.1-3.0	7
C@ZnO nanorod arrays on alloy	9.4	0.1	<4	0.1-3.8	7
Flower-like microstructure ZnO	0.095	2.1	<4	3.0-120	8
Hierarchical micro/nanoarchitecture ZnO	0.51	0.25	<3	0.8-200	8
ZnO NRs based FET	59.175	~0.00386	~4	0.001-60	This work

4. Reference

1. Umar, M.M. Rahman, S.H. Kim and Y.B. Hahn, *Chem. Communi.*, 2008, 166-168.
2. Umar, M.M. Rahman and Y.B. Hahn, *J. Nanosci. Nanotech.*, 2009, **9**, 4686-4691.
3. S. Ameen, M. S. Akhtar, and H. S. Shin, *Talanta*, 2012, 100, 377-383.
4. S.K. Mehta, K. Singh, A. Umar, G.R. Chaudhary and S. Singh, *Electrochimica Acta*, 2012, **69**, 128-133.
5. B. Fang, C. Zhang, W. Zhang and G. Wang, *Electrochimica Acta*, 2009, **55**, 178-182.
6. J. Liu, Y. Li, J. Jiang and X. Huang, *Dalton Trans.*, 2010,**39**, 8693-8697.
7. Y. Ni, J. Zhu, L. Zhang and J. Hong, *CrystEngComm*, 2010, **12**, 2213-2218.